

Monday, June 4

Selective Deposition Workshop

Workshop Chairs: Larry Zhao, Terry Spooner

8:15 am

Welcome and Introductions

8:30 am

Selective Deposition Challenges and Opportunities for Patterning, Efrain Altamirano-Sanchez

9:20 am

Selective Metal CVD and Nano Fabrication Applications, Son Van Nguyen

10:10 am

BREAK

10:40 am

Selective Processes: Challenges and Opportunities in Semiconductor Scaling, Kandabara Tapily

11:30 am

Substrate-selective Reactions in Atomic Layer Deposition and Atomic Layer Etching, Greg Parsons

12:20 pm

LUNCH

1:20 pm

Area and Topographical Selectivity in Atomic Layer Deposition, Stacey Bent

2:10 pm

Precursor and Inhibitor Design for Selective ALD/CVD, Jean-Marc Girard

3:00 pm

BREAK

3:30 pm

A Tutorial on Electrochemical Atomic Layer Deposition: How Electrochemistry Enables Atomically-Precise and Selective Deposition of Metals, Rohan Akolkar

4:10 pm

Selective Electroless Deposition: Process, Challenges, and Solutions and its Critical Role in RC Scaling, Artur Kolics

5:10 pm

WORKSHOP ENDS